



PRESS RELEASE

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LEADING EXPERTISE IN ALD AND NANOTECHNOLOGY

Picosun's new Board of Directors has been appointed

HELSINKI, Finland – June 20, 2007 - The annual Shareholders' Meeting of Picosun Oy has elected Prof. Jorma Routti, Prof. Lauri Niinistö, and Dr. Tuomo Suntola as new Board members. All the old members continue in the Board.

Professor, Ph.D Jorma Routti is one of the founders of Finnish venture capital and one of Europe's leading technology experts. Professor Routti is the Chairman of Creative Industries Management Ltd. and has managed Knowledge Economy Projects at World Bank since 2003. Professor Routti was Director General of Research at the European Commission from 1985 to 2000. His long career also includes heading the Finnish National Fund for Research and Development (SITRA), being the Dean of Helsinki University of Technology, and a visiting scientist at CERN, Geneva. At SITRA he made numerous private placements in Finnish and international technology companies, several of which were successfully floated. His numerous honors include a Fulbright Fellowship, an Eisenhower Exchange Fellowship, and Chevalier dans l'ordre des Palmes Academiques, France. He holds a Ph.D from UCB Berkeley and several honorary doctorates.

Professor, Dr. Tech. Lauri Niinistö is one of the key persons in developing Atomic Layer Deposition processes and applications in Academia since late 1970s. He has more than 500 original publications and reviews on inorganic, analytical and materials chemistry, several textbooks (in Finnish), articles on the history of chemistry. His most recent research is focused on the preparation and characterization of thin films and overlayers for electronic, catalytic and sensor applications. He has acted as a visiting Professor at University of Florida in 1985 – 86, Technical University of Vienna in 1993 and at Budapest University of Technology and Economics in 2000. His career includes heading of several organizations and societies, such as Finnish Chemical Society, Federation of European Chemical Societies (FECS), FECS Working Party on Analytical Chemistry (since 1997: Division of Analytical Chemistry) and European Rare Earth Research Society (ERES). He is the editor or editorial board member of several Scientific Journals. His numerous recognitions and awards include Stanislao Cannizzaro Gold Medal of the Italian Chemical Society and FECS Award. He holds a Dr. Tech. from Helsinki University of Technology and two honorary doctorates.

Dr. Tech. Tuomo Suntola is the inventor of ALD method and Executive Advisor of Picosun Oy through Suntola Consulting Ltd. since the start of Picosun. Dr. Suntola introduced ALD with potential to electro-luminescent flat panel display application in 1974 – 1977. He was the initiator and the head of flat panel display division at Lohja Oy in 1977 – 1987 and the founder and Directing Manager of Microchemistry Ltd. in 1987 – 1997. Dr. Suntola has developed ALD for industrial production of electroluminescent flat panel displays and started the expansion of ALD technology to semiconductor applications and catalytic surface fabrication. Dr. Suntola was R&D Fellow at Neste Oy and Senior Scientific Advisor at Fortum Oyj 1998 – 2003. His current research has emphasis on sustainable energy future. Dr. Suntola is the author of numerous publications and patents regarding ALD, Thin Film Devices, Photovoltaics, renewable energy, climate change and fundamentals of Physics. His numerous honors and awards include The Finnish Engineering Achievement Award 1985 for Electroluminescent Display Technology and 2001 and European SEMI Award 2004, for the development of the ALD technology to semiconductor applications. Dr. Suntola is Knight 1st Class of the Order of the Lion of Finland and holds a Dr. Tech. from Helsinki University of Technology.

Picosun Oy, a Finnish company started in Espoo in 2003, develops and manufactures ALD reactors for nanotechnology applications. Atomic Layer Deposition (ALD) is a thin film deposition method that has been developed in Finland since 1974. ALD technology enables thin-film coating of nanosize structures and objects with a desired film thickness, conforming to the shapes of the surface precisely. ALD method has been applied successfully in manufacturing thin displays, microprocessors, mass memories, solar panels and catalytic materials.

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